

## ABSTRACT

**Lithographic Apparatus, Support, Device Manufacturing Method, and a Method of Supporting**

A lithographic apparatus comprising:

- an illumination system configured to condition a radiation beam;
- a support constructed to support a patterning device, the patterning device being capable of imparting the radiation beam with a pattern in its cross-section to form a patterned radiation beam; wherein the support is arranged to subject, at least when the support is accelerated, a first side of the patterning device to at least one first force normal to the direction of the acceleration so that an acceleration of the patterning device with respect to the support is counteracted by frictional forces occurring at a contact area between the patterning device and the support, wherein the support is associated with a clamping device which is arranged to subject a second side of the patterning device to at least one second force, at least when the support is accelerated.